

## Supporting Information

# Selective Nitrogen Doping in Graphene for Oxygen Reduction Reactions

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## Experimental section

**Materials.** Nitrogen-doped graphene was grown on Cu foils (99.999%, 25  $\mu\text{m}$  in thickness, Alfa Aesar) or Cu disks (99.99%, 5 mm in diameter, Niraco) using pyridine and julolidine as nitrogen-containing aromatic precursor molecules (Wako Pure Chemical). Prior to film growth, the Cu foils and Cu disks were annealed at 900  $^{\circ}\text{C}$  for 30 min in  $\text{H}_2$  (flow rate: 300 sccm) to remove residual organics and oxides from the surface. Pyridine-based graphene was grown on the Cu surface by flowing saturated pyridine vapor gas with Ar (flow rate: 50 sccm) at the desired temperature (typically 400–600  $^{\circ}\text{C}$ ) for 0.5–3 h. To prepare the julolidine-based graphene, julolidine powder was first heated at 100  $^{\circ}\text{C}$ , and then the julolidine-based graphene was grown on a Cu substrate at the desired temperature (typically 400–600  $^{\circ}\text{C}$ ) for 0.5–4 h under flowing Ar gas (rate: 50 sccm).

At growth temperature in the range of 400–600  $^{\circ}\text{C}$ , no visible soot was observed inside wall of the furnace when saturated pyridine-Ar or julolidine-Ar vapor gases were introduced. The results imply that the temperature range could inhibit the pyrolysis of the precursor molecules.

**Characterization.** Raman spectra were recorded on a micro-Raman spectrophotometer (Thermo Fisher Scientific), equipped with a 532-nm laser. A laser power of <1 mW was used to avoid damage of the samples by laser-induced heating. Atomic force microscopy images were acquired in

tapping mode, in air, on a Veeco Digital Instruments Nanoscope IIIa. X-ray photoelectron spectroscopy was performed on a JEOL JPS-9200, using a monochromatic Al K $\alpha$  X-ray source (1486.6 eV). Electrochemical measurements were carried out in a three-electrode cell with a Pt wire and Ag/AgCl (saturated KCl solution) as the counter and reference electrodes, respectively. The nitrogen-doped graphene, grown on the Cu disk, was used as the working electrode. The working electrode was supported onto a glassy carbon disk electrode, using a silver paste. The rim of the combined electrodes was carefully sealed with an acrylic resin. This process enables electrochemical measurements of the surface of the grown disk only.

**Film transfer and morphology measurements.** To assess film thickness and morphology by atomic force microscopy, grown samples on Cu foils were transferred to Si wafer substrate with 300 nm SiO<sub>2</sub> layer using PMMA coating and chemical etching technique as previously reported.<sup>1,2</sup> A protective thin film was deposited on the backside of the foils using 5 % polymethyl methacrylate (PMMA) dissolved in toluene. The frontside of the foil was etched away by floating the foils on 0.1 M (NH<sub>4</sub>)<sub>2</sub>S<sub>2</sub>O<sub>8</sub> solution for 12 h at room temperature. After several washing by DI water, the PMMA-coated films were transferred to the SiO<sub>2</sub>/Si substrate and completely dried in an oven at 60 °C for a few hours. Finally, the PMMA protective layers were removed by immersing the samples in a large volume of acetone at room temperature.

**Oxygen reduction reaction (ORR) activity and measurements.** The ORR studies were conducted in an O<sub>2</sub>-saturated KOH aqueous solution (0.1 M) using a rotating disk electrode system (Hokuto). Prior to ORR measurements, the solution was bubbled with O<sub>2</sub> for 1 h.

The transferred electron numbers per oxygen molecule involved in the ORR were determined using the Koutechy–Levich equation as follows:

$$\frac{1}{J} = \frac{1}{J_K} + \frac{1}{J_L} = \frac{1}{J_K} + \frac{1}{B\omega^{0.5}}, \quad (\text{Eq. S1})$$

where  $J$  is the measured current density,  $J_K$  and  $J_L$  are the kinetic- and diffusion-limiting current densities,  $B$  is the Levich constant, and  $\omega$  is the electrode rotating rate. The transferred electron numbers per oxygen molecule can be calculated from the Levich constant as follows:

$$B = 0.62nFD^{2/3}\nu^{-1/6}C_0, \quad (\text{Eq. S2})$$

where  $n$  is the transferred electron numbers per oxygen molecule,  $F$  is the Faraday constant ( $F = 96485 \text{ C mol}^{-1}$ ),  $D$  is the diffusion coefficient of O<sub>2</sub> in 0.1 M KOH (*i.e.*,  $1.9 \times 10^{-5} \text{ cm}^2 \text{ s}^{-1}$ ),  $\nu$  is the kinetic viscosity ( $0.01 \text{ cm}^2 \text{ s}^{-1}$ ), and  $C_0$  is the bulk concentration of oxygen (*i.e.*,  $1.2 \times 10^{-3} \text{ mol L}^{-1}$ ).

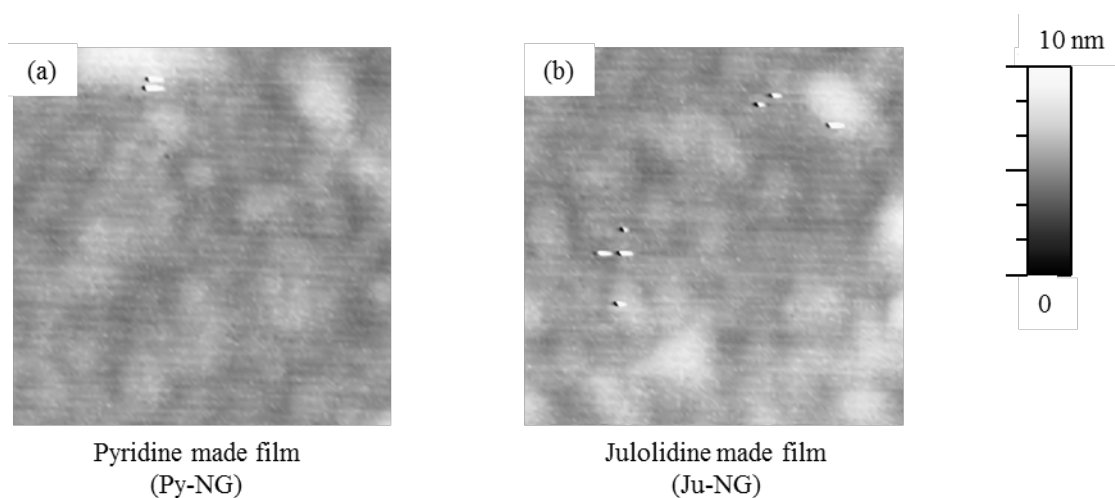


Fig. S1. Enlarged atomic force microscopy images of (a) pyridine-based graphene film and (b) julolidine-based graphene film.

|             | Pyridine made film<br>(Py-NG) | Julolidine made film<br>(Ju-NG) |
|-------------|-------------------------------|---------------------------------|
| N / C ratio | 0.027                         | 0.023                           |

Table S1 relative nitrogen/carbon (N/C) ratio for Py-NG and Ju-NG

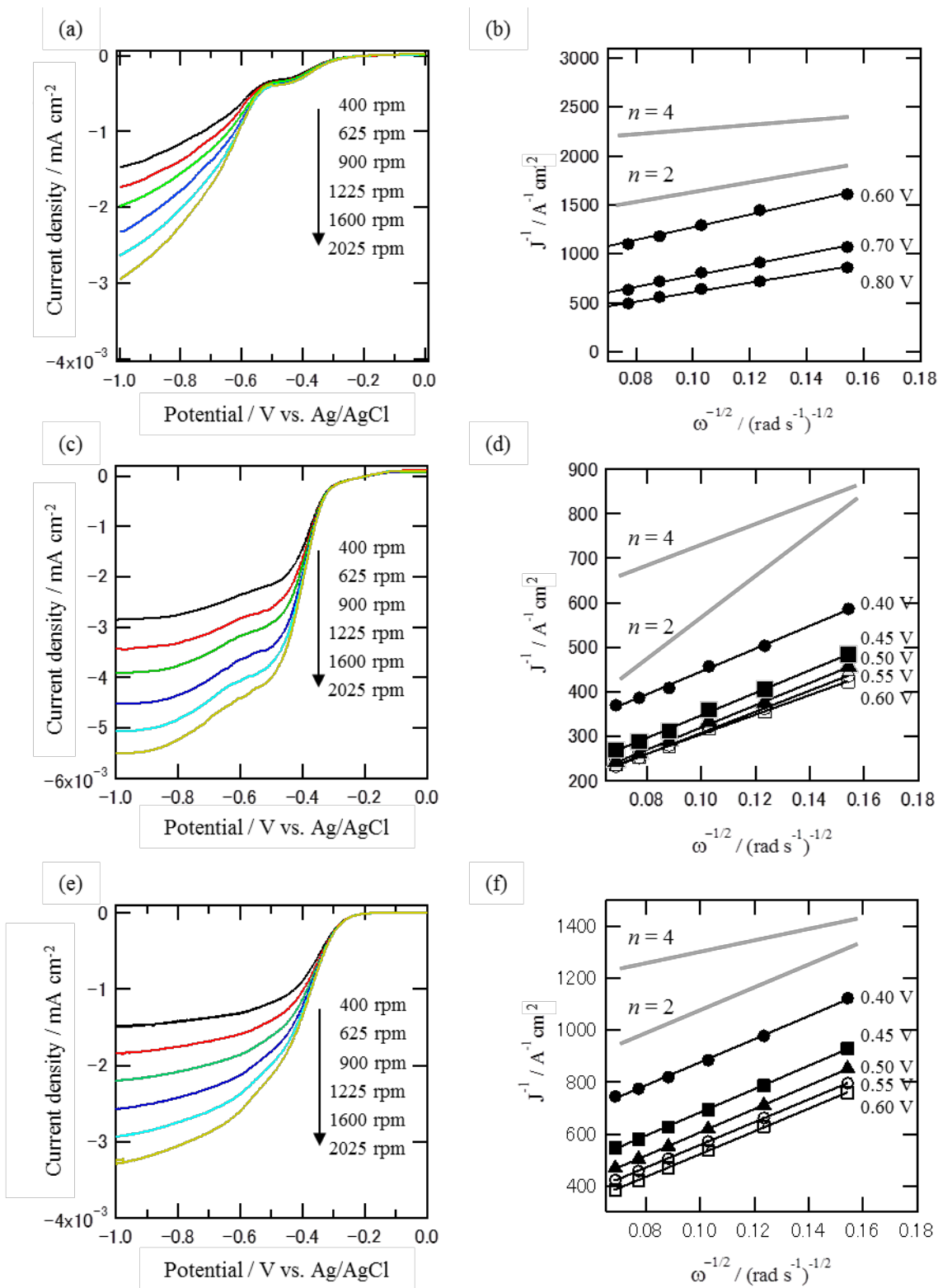


Fig. S2. Rotating disk electrode voltammetry curves of (a) pristine graphene, (c) pyridine-based graphene, and (e) julolidine-based graphene films. Koutechy–Levich plots of (b) pristine graphene, (d) pyridine-based graphene, and (f) julolidine-based graphene films.

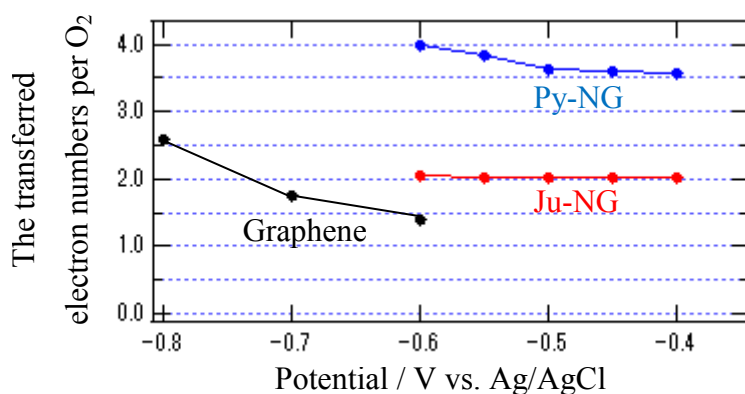


Fig. S3. Potential dependence on transferred electron numbers per O<sub>2</sub> for graphene, Py-NG, and Ju-NG.

## References

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